

**MONITOR FOR VARIATION
OF CRITICAL DIMENSIONS (CDs) OF RETICLES**

ABSTRACT OF THE DISCLOSURE

The present invention provides a reticle 100 for use in a lithographic process. The reticle, in one embodiment, includes a patterned layer 110 located over a reticle substrate. The reticle 100 may further include a test pattern 130 located over the reticle substrate, wherein a portion of the test pattern 130 is within a step-distance of a portion of the patterned layer. In this embodiment, a variance in the test pattern is indicative of a variance in the patterned layer.